



제 30회 한국반도체학술대회

The 30th Korean Conference on Semiconductors

2023년 2월 13일(월) ~ 15일(수) | 강원도 하이원리조트(그랜드호텔 컨벤션타워)

2023년 2월 15일(수), 10:45-12:30

Room H (하트 I, 6층)

B. Patterning (Lithography & Etch Technology) 분과

[WH2-B] Advanced Etch Technology II

좌장: 김창구 교수(아주대학교), 조성일 상무(삼성전자)

WH2-B-1 10:45-11:15 [초청]	Novel Approach to Remove NVM(non-volatile metal) Selectively-atomistically-isotropically YS(Yunsang) Kim SEMES Co., Ltd.
WH2-B-2 11:15-11:45 [초청]	Etch 공정 중 사용되는 소모재에 대한 ESG 관점의 고찰 Yeonghun Han and Jungtaik Cheong Semiconductor R&D, SK Hynix
WH2-B-3 11:45-12:00	2차원 물질의 무손상 원자층 단위 식각 기술에 대한 연구 Dongryul Lee ¹ , Geonyeop Lee ¹ , and Jihyun Kim ² ¹ Department of Chemical and Biological Engineering, Korea University, ² School of Chemical and Biological Engineering, Seoul National University
WH2-B-4 12:00-12:15	Surface Reaction during Isotropic Atomic Layer Etching of Al₂O₃ Using NF₃ Remote Plasma and Al Precursor Yewon Kim ¹ , Gyejun Cho ¹ , Okhyeon Kim ¹ , Khabib Khumaini ^{1,2} , Hye-Lee Kim ³ , Jun Hyuck Kwon ⁴ , Minsu Kim ⁴ , Byungchul Cho ⁴ , Sangjoon Park ⁴ , and Won-Jun Lee ^{1,3} ¹ Department of Nanotechnology and Advanced Materials Engineering, Sejong University, ² Department of Chemistry, Universitas Pertamina, ³ Metal-organic Compounds Materials Research Center, Sejong University, ⁴ Wonik IPS
WH2-B-5 12:15-12:30	BCl₃/Cl₂ Plasma Etching Process of Ferroelectric Gate Stack for Device Integration Bohyeon Kang, Sung-min Ahn, Jongseo Park, Jehyun An, Hyunseo You, and Rock-Hyun Baek Department of Electrical Engineering, POSTECH